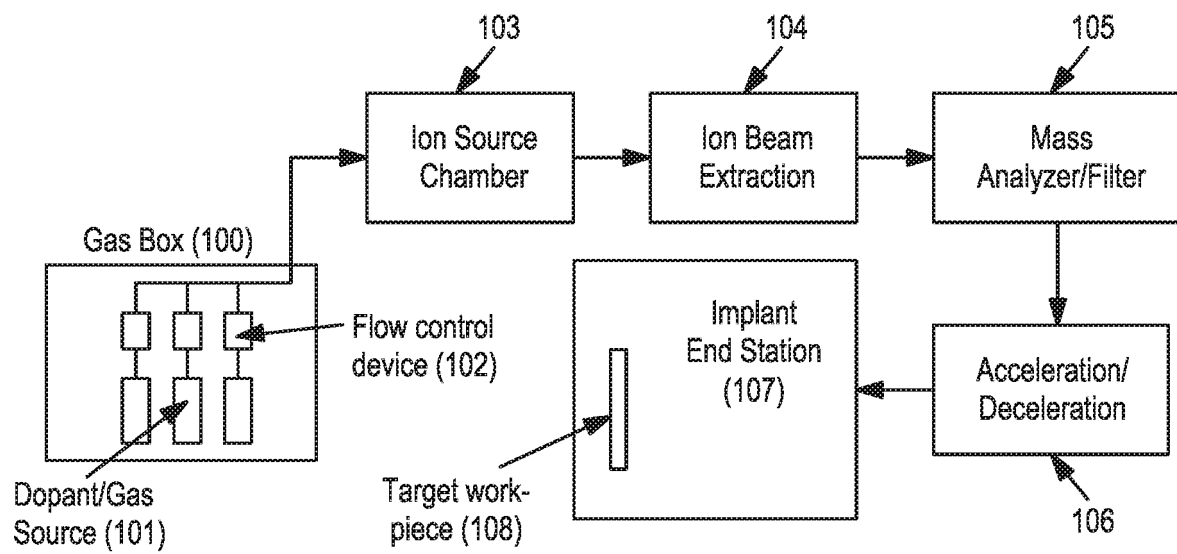
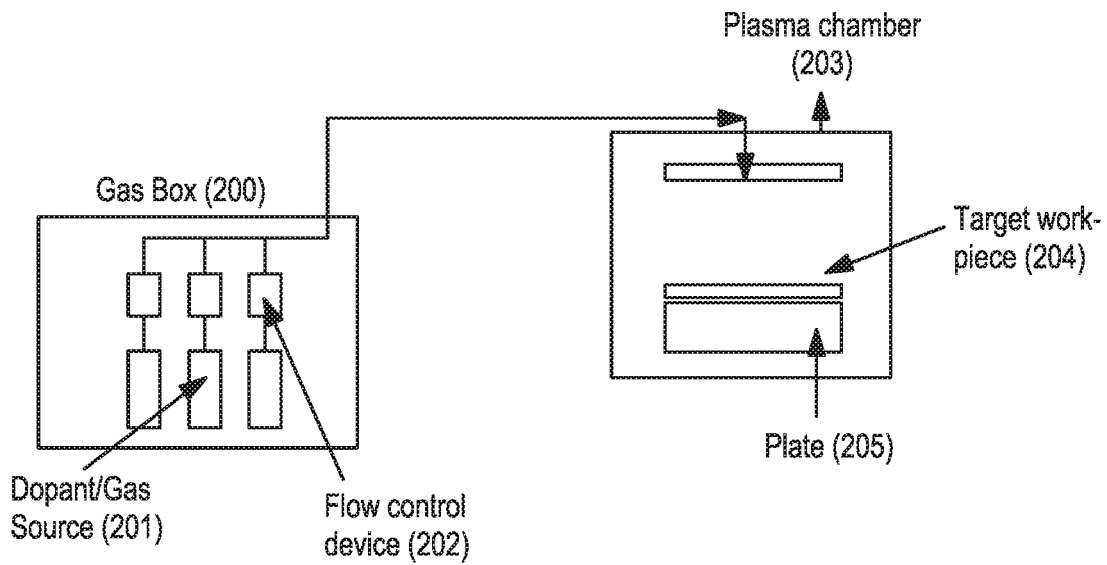
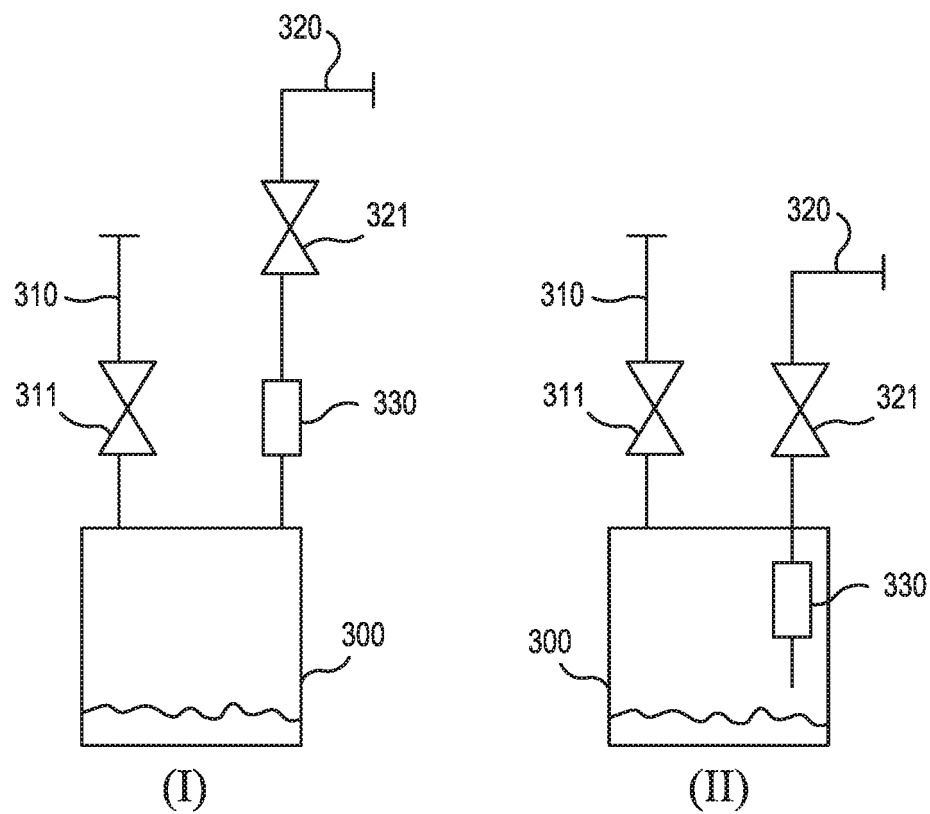


**FIG. 1**

Schematic of beamline ion implant system

**FIG. 2**

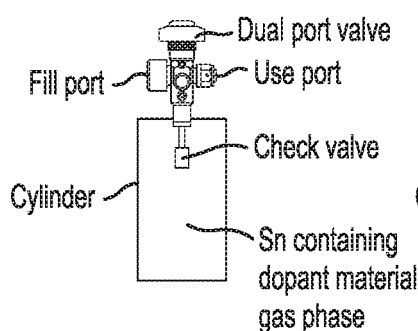
Schematic of plasma immersion ion implant system

**FIG. 3a**

Package for Sn dopant materials

FIG. 3b

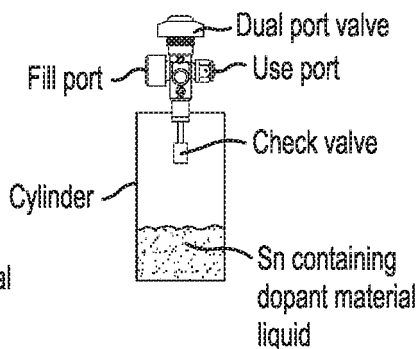
Package for Sn dopant materials



Case 1

FIG. 4a

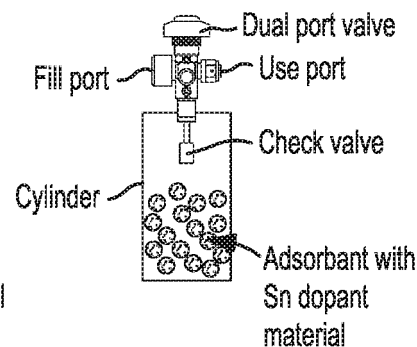
Examples of storage and delivery package for three separate states of Sn dopant source



Case 2

FIG. 4b

Examples of storage and delivery package for three separate states of Sn dopant source



Case 3

FIG. 4c

Examples of storage and delivery package for three separate states of Sn dopant source

CAS Number	CAS Index Name	Formula	Vapor Pressure at 25°C in Torr
3582-18-1	Stannane, trifluoromethyl- (9Cl)	F_3SnCH_3	1280
51105-30-7	Stannane, ethenyltrifluoro-	$F_3SnCH=CH_2$	499
65059-36-1	Stannane, dimethylbis(trifluoromethyl)-	$(CH_3)_2Sn(CF_3)_2$	449
51105-29-4	Stannane, ethyltrifluoro-	$F_3SnCH_2CH_3$	382
754-25-6	Stannane, trimethyl(trifluoromethyl)-	$(CH_3)_3SnCF_3$	115
812-35-1	Stannane, trimethyl(1,1,2,2,2-pentafluoroethyl)-	$(CH_3)_3SnCF_2CF_3$	84
815-22-5	Stannane, trimethyl(1,2,2-trifluoroethenyl)-	$(CH_3)_3SnCF=CF_2$	66.3
649-48-9	Stannane, diethyldifluoro-	$F_2Sn(CH_2CH_3)_2$	49.5
51105-28-3	Stannane, butyltrifluoro-	$F_3SnCH_2CH_2CH_2CH_3$	38.8
594-27-4	Stannane, tetramethyl	$Sn(CH_3)_4$	120
41268-44-4	Stannane, tetrakis (trifluoromethyl)	$Sn(CF_3)_4$	1930
7646-78-8	Stannane, tetrachloro	$Sn(Cl)_4$	20
1066-99-5	Stannane, dimethoxy dimethyl	$(CH_3)_2Sn(OCH_3)_2$	45
1070-81-1	Stannane, Ethoxy trimethyl	$(CH_3)_3SnOCH_2CH_3$	20
1066-58-6	Stannane, Methoxy Trimethyl	$(CH_3)_3SnOCH_3$	60.1
185839-03-6	Stannane, Dichloromethoxymethyl	$CH_3SnCl_2OCH_3$	23.7

FIG. 5

Table Sn containing dopant sources